

# Valley currents via ballistic edge modes in graphene superlattice near the main Dirac point

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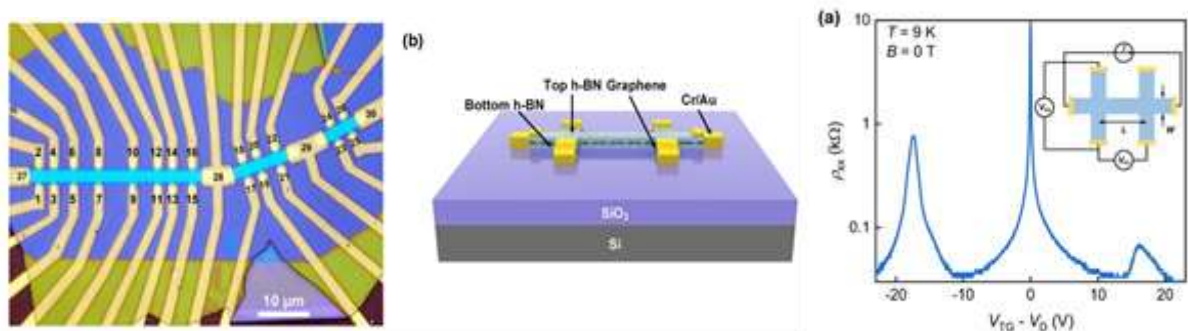
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In carefully stacked two-dimensional materials, topological bands generate Hall like conductivity and topologically protected edge states in zero magnetic field. By placing single layer graphene (SLG) on hexagonal boron nitride (h-BN), it might be possible to transform SLG into a topological phase by varying their crystallographic alignment. Recent measurements of nonlocal resistances ( $R_{nl}$ ) [1] in a narrow energy range focusing with the secondary Dirac point (SDP) [2] in SLG/h-BN superlattice Hall bars have been interpreted as arising due to the valley Hall effect and quantum valley Hall state. Here we report h-BN/SLG/h-BN Hall bars which have a negligible  $R_{nl}$  of SDPs, but at the main DP  $R_{nl}$  is reaching quantum-limit at 9 K. We investigate valley currents near the main Dirac point [3] and also demonstrate nonlocal measurements over a distance of 15  $\mu\text{m}$  indicating ballistic behaviour in good agreement with recent theoretical works [4] that are trying to shed some light into these intriguing experiments.

## REFERENCES

- [1] C.R. Woods, L. Britnell, et al., Nature Physics 10 (2014) 451.
- [2] G.L Yu, R.V. Gorbachev et al. Nature Physics 10 (2014) 525.
- [3] Y. Li, M. A., et al. Communications Physics 3 (2020) 224
- [4] T. Aktor, J. H Garcia, S.roche et al. Physical Review B 103 (2021) 115406.

## FIGURES



**Figure 1:** From left to right, h-BN/SLG/h-BN device structure via optical micrograph, schematic illustration of a typical device, Longitudinal resistivity ( $\rho_{xx}$ ) vs gate voltage ( $V_{TG} - V_D$ ) in zero magnetic field at 9 K. Inset shows schematic illustrations of the local measurement setup, where  $L$  is the distance between the current path and voltage probes, and  $W$  is the device width.